Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	12831	(@ad<"20040217") and ((sidewall$1 and polysilicon) with (gate or gates))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 13:54
L2	9262	L1 and (dielectric or insulation or insulate or insulating or isolate or isolation or isolating) and ((etch or etching or etchant) with (polysilicon or gate))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 16:10
L3	6297	L2 and substrate	USPAT	OR	OFF	2005/06/16 14:08
L4	907	l3 and (((anneal or heat or heating or furnace) and silicide) with (gate or gates or polysilicon))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 16:09
L5	600	L2 and (recess with (polysilicon or gate))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 14:07
L6	388	L5 and substrate	USPAT	OR	OFF	2005/06/16 14:08
L7	334	L6 not L4	USPAT	OR	OFF	2005/06/16 14:08
L8	472	l4 and ((anneal or heat or heating or furnace) with silicide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 16:09
L9	1348	l3 and (((annealing or anneal or heat or heating or furnace) and silicide) with (gate or gates or polysilicon))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 16:09
L10	778	l9 and ((annealing or anneal or heat or heating or furnace) with silicide)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 16:09

L11	722	L10 and ((etch or etching or etchant) with gate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/06/16 16:30
L12	3	(("6465309") or ("6475908") or ("6528402")).PN.	USPAT	OR	OFF	2005/06/16 16:30